

Figure 1. a) *Ex situ* XRF data showing the selective decomposition of TDMASn on Pt thin films. The TDMASn was pulsed into the reactor in discrete pulses, followed by a pumping step after each exposure. **b)** XRD patterns showing the formation of different Pt-Sn alloys after the TDMASn introduction to Pt.



Figure 2. SEM images of the **a**) ALD synthesized Pt NPs , **b**) the same Pt NPs after TDMASn-H₂ process, and **c**) Pt NPs after the TDMASn only process (right). The white scale bars indicate 200 nm. The similar morphologies of Pt and after the TDMASn-H₂ conversion process is evident.



Figure 3. a) *In situ* XRF data showing the variation of Sn/(Sn+Pt) atomic ratio of TDMASn-H₂ process on a 3 nm (equivalent thickness) ALD Pt substrate at 150°C, 200°C, and 250°C. **b)** Corresponding XRD data showing the different alloys formed.